

CLEAN VERSION OF THE CHANGES MADE

In the Claims

Claims 1-5, 7 and 8 are pending in the application as follows:

1. A method for providing a raised feature on a surface of a prototype model characterized by the steps of:

(a) providing a model formed by a stereolithography process, the model having at least one surface on which to provide a raised feature;

(b) coating the surface with a photo resist to a predetermined thickness;

(c) providing means for preventing exposure of a first portion of the photo resist to a radiation source while allowing exposure of a second portion of the photo resist wherein the second portion of the photo resist provides the raised feature;

(d) exposing the surface to a radiation source to chemically alter the second portions of the photo resist; and,

(e) removing the first portion of the photo resist from the surface while leaving the raised feature formed by the exposed photo resist on the surface.

2. The method of claim 1 wherein the step of coating the surface with a photo resist is further characterized by the steps of applying the photo resist in more than one layer.

3. The method of claim 2 further characterized by the step of:
allowing sufficient drying time between successive layers of the photo resist.

4. The method of claim 1 further characterized by the step of:
cleaning the surface of the prototype model before the step of coating the surface with the photo resist.

5. The method of claim 1 further characterized by the steps of:

inspecting the raised feature after the step of removing the first portion of the photo resist; and,

repeating steps (b) - (e) to enhance the raised feature.

12 7. A prototype model having a raised feature on at least one surface wherein the raised feature is formed by the method of claim 1.

8. The method of claim 1 further characterized by the step of:

A2 softening an edge of said raised feature by over-coating said edge with additional photo resist.
